

Cancelled

at least one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages, wherein:

 said polishing cloth has a flat plate portion;

 said polishing projections are formed as projecting from said flat plate portion;

 said polishing agent passages are formed by grooves formed in said flat plate portion; and

the surface of said flat plate portion forms said step portions.

6. (Once Amended) A chemical mechanical polishing apparatus comprising:
 a chemical mechanical polishing cloth for chemically mechanically polishing a workpiece;

 a polishing head for holding and rubbing a workpiece with said chemical mechanical polishing cloth; and

 a polishing agent supply mechanism for supplying a polishing agent to said chemical mechanical polishing cloth,

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 said mechanical polishing cloth including, on an opposite-to-workpiece face thereof:

 polishing projections having polishing faces arranged to come in contact with a workpiece for polishing same;

 polishing agent passages, having bottoms, for introducing a polishing agent; and
 at least one-stage step portions formed between said polishing faces of said polishing projections and the bottoms of said polishing agent passages, wherein

 said polishing cloth has a flat plate portion;

 said polishing projections are formed as projecting from said flat plate portion;